

Effect of substrate temperature on some structural and optical properties of ZnTe films

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Abstract

Zinc telluride thin films of various thickness are deposited onto clean corning glass substrates kept on different temperatures ($T_s=323,393$ and 473 k), by vacuum evaporation method under the pressure of 10^{-5} Torr. The thickness of the films were measured by optical interference method (Tolansky). All the films prepared at different substrate temperatures were studied by X-ray diffraction method and shown that ZnTe films with (100nm) thickness have single crystal structure at substrate temperatures (323,393k) and polycrystalline structure at substrate temperature (473k), while we show that the films with (160 nm) thickness have single crystal at substrate temperature (323k) and polycrystalline structure at substrate temperatures (393,473k). Optical behaviour of the films were analyzed from transmittance spectra in the visible region (400-800 nm). The optical transition in ZnTe films is direct and allowed type. The optical band gap energy shows an inverse dependence on substrate temperature and thickness.

تأثير درجة حرارة الاساس على بعض الخصائص التركيبية والبصريه لاغشية ZnTe
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الخلاصه:

تم ترسيب اغشيه رقيقه باسمك مختلفه على قواعد من الزجاج النظيف نوع (Corning) بدرجات حرارة اساس مختلفه ($T_s=323,393$ and 473 k) بطريقة التبخير الحراري في الفراغ تحت ضغط (10^{-5} Torr). تم قياس سمك الاغشيه المحضره بطريقة التداخل الضوئي (تولانسكي). تم دراسة الخصائص التركيبية للاغشيه المحضره باستخدام تقنية حيود الاشعه السينيه ووجد ان الاغشيه ذات السمك ((100 nm احادية التبلور عند درجة حرارة اساس (323,393k) ومتعددة التبلور عند درجة حرارة الاساس (473k) ، بينما وجد ان الاغشيه ذات السمك (160nm) احادية التبلور عند درجة حرارة اساس (323k) ومتعددة التبلور عند درجة حرارة اساس (393,473k)). الخصائص البصريه للاغشيه تم دراستها من خلال طيف النفاذيه ضمن المنطقه المرئيه (400-800nm) اظهرت القياسات البصريه بان اغشيه ZnTe تمتلك فجوة طاقه مباشره ذات انتقال مسموح. كما لوحظ ان فجوة الطاقه تتناسب عكسيا مع درجة الحرارة والسمك.

Introduction .1

Zinc telluride (ZnTe) is an important semiconductor material for the development of various modern technologies of solid state devices (blue light emitting diodes, laser diodes, solar cells, microwave devices, etc) [1-4]. The 11-V1 compound semiconductors have considerable potential for Integrated-optics applications due to their high electro-optics coefficients, wide transparency range from the visible beyond to $10 \mu\text{m}$ [5]. Zinc Telluride (ZnTe) is a 11-V1 compound semiconductor with Zinc-blend structure with lattice constant of 6.1037 \AA , direct band gap of 2.26 eV at room temperature [6], and melting point of 1295°C . ZnTe and its alloys may effectively be used as window materials in CdTe heterojunction solar cells. These thin films were also

used in tandem solar cell structure, which utilizes CdZnTe as the absorber material, and for the fabrication of a CdZnTe/ZnTe quantum well structure [7]. Since optical response is of great importance for many device applications, much work has been done to determine the reflectivity, band gaps, and refractive index of ZnTe. Because of its importance several works [8] have made a detailed study on structure of ZnTe thin films. They have observed that these films deposited on glass substrates kept at room temperature have cubic Zinc-blende type structure. Saleem [9] has carried out studies on the optical properties on ZnTe thin films and calculated the optical constants. Raheem G.K [10] has measured structural properties of ZnTe which used as heterojunction as CdTe_{1-x}Se_x/ZnTe. A theoretical model has been proposed by Pawlikowski [11] for ZnTe films and he determined the absorption coefficient near the fundamental absorption edge at normal incidence. Mondal et al. [12] have reported the dependence of refractive index, absorption and extinction coefficients on incident photon energy ($h\nu$) for ZnTe films deposited on glass substrates by hot wall evaporation technique. Akkad and Thomas [13] have prepared ZnTe-cu thin films and measured the room temperature transmission and reflectivity in the wavelength range 300 nm. Rusu et al. [14] have deposited ZnTe thin films ($d=0.12-180 \mu\text{m}$) onto glass substrates by the quasi-closed volume technique under vacuum of 10^{-5} Torr. Optical gap was calculated from the absorption spectra situated in the range of (1.70-2.40) eV. However not much work has been carried out on substrate temperature and optical properties of ZnTe films and their dependence on substrate temperature (T_s). Hence, this paper reports about the temperature dependence of structural, and optical properties of vacuum evaporated ZnTe thin films.

Experimental details

The bulk ZnTe alloy was prepared from its own constitutional elements. Appropriate weights of Zn and Te were mixed together, charged in a quartz tube and sealed under a vacuum of 10^{-5} Torr. The sealed quartz ampoule with the charge was placed in a rotating furnace. The temperature of the furnace was raised gradually to 1523 K and left at this temperature for about three hours with a rate of $5^\circ/\text{min}$ using a programmable furnace type carbolite. After that the ampoule was cooled down in furnace and then broken to bring out the alloy.

Thin films of ZnTe were prepared by thermal evaporation using an Edward E306A coating unit onto cleaned glass substrates maintained at various temperatures ($T_s=323, 373$ and 473K) during evaporation. A Molybdenum boat was used as the source holder and the pressure in the chamber was of order (2×10^{-6}) mbar. The ZnTe films were evaporated thermally with a deposition rate of 0.5 nm/s with (100 and 160) nm thicknesses. The thicknesses of the films were evaluated using a Fizeau interferometric method. The structural aspects of the films were analyzed, using X-ray diffractometer with filtered $\text{CuK}\alpha$ radiation ($\lambda=1.5418 \text{\AA}$). The optical transmittance spectra of these films were recorded using UV-VIS-NIR spectrometer.

Results and discussion 3

structural characteristics 3-1

The XRD patterns show different crystalline phases depending on the substrate temperature. At lower temperatures, the (111) peak is predominant, while at higher temperatures, the (220) and (311) peaks become more prominent. This indicates a change in the crystal structure and grain size as the substrate temperature increases.

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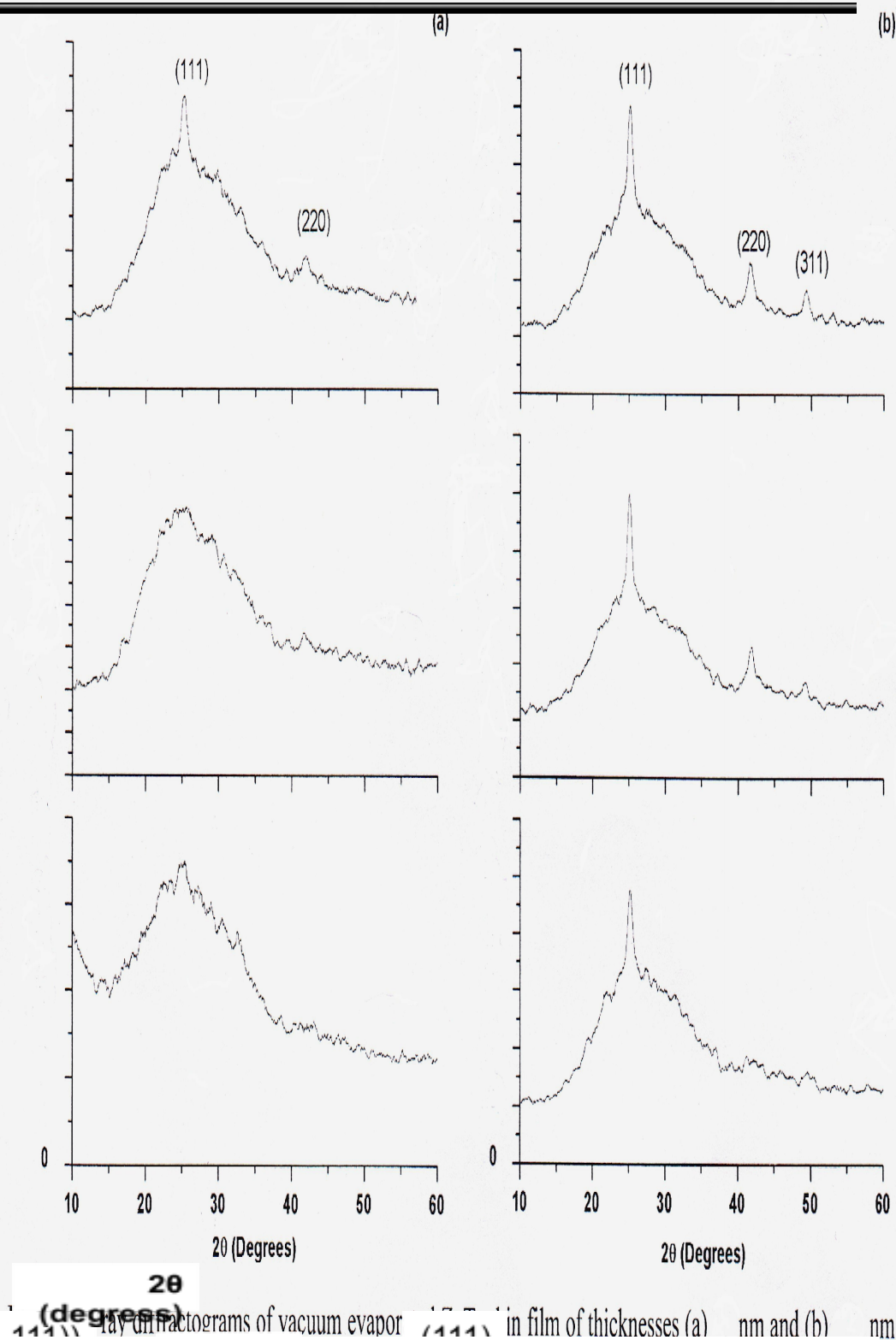


Fig.1 XRD spectra of ZnTe thin films of thickness (a) 100 nm and (b) 160 nm deposited at different substrate temperature

The decrease in grain size at higher substrate temperature may be due to the some Zn reevaporation, which changes the stoichiometric, leaving an excess of Te on the film, which forms crystalline grains. This is a consequence of the large surface area of the atoms at high temperature; thus, there is a decrease in the density of the atoms at high temperature, and under these circumstances a smaller number of centers start to grow. A decrease in grain size at higher substrate temperature may be due to the some Zn reevaporation, which changes the stoichiometric, leaving an excess of Te on the film, which forms crystalline grains.

Table 1 structural parameters of ZnTe films

| (Thickness(Å | (T _s (k | Lattice constant a(Å | Grain size D(Å | hkl |
|--------------|--------------------|----------------------|----------------|-----|
| 1000 | 443 | 6.230 | 92 | 111 |
| 1600 | 323 | 552 .6 | 158 | 111 |
| | 393 | 6.560 | 175 | 111 |
| | 443 | 6.572 | 146 | 111 |

Optical properties 3-2

The transmittance spectra for ZnTe thin film of thickness 1000Å and 1600Å deposited at various substrate temperatures(T_s=323,373 and 443 k) are shown in figure 2.It is clearly observed that the film has very low transmittance in the visible region and further increases to higher values at higher wavelength region.The transmittance falls steeply with decreasing wavelength.It can be positively concluded that the material is of highly absorbing nature in the visible region (4000-8000Å).This is in good agreement with the earlier investigation[].For the semiconducting films with with the thickness below 1000Å important role in the optical absorptrion(transmission)also begin to play non-confined effects on the borders film-substrate and amorphous-like background-microcrystallites,how it was shown during investigations of the optical and non-linear optical properties of the ZnS doped films[15].These nano-confined levels also may cause observed short wavelength .shift of spectra

The total absorption coefficient was calculated from transmittance measurements :[with the aid of the expression[16

$$\alpha = \left(\frac{4\pi k_f}{\lambda} \right) \quad (1) \dots\dots\dots$$

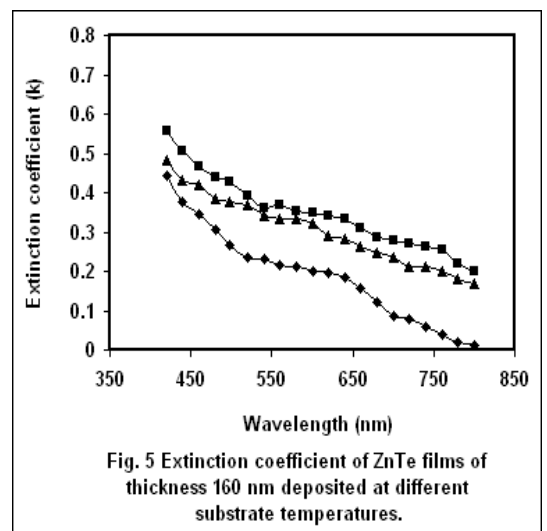
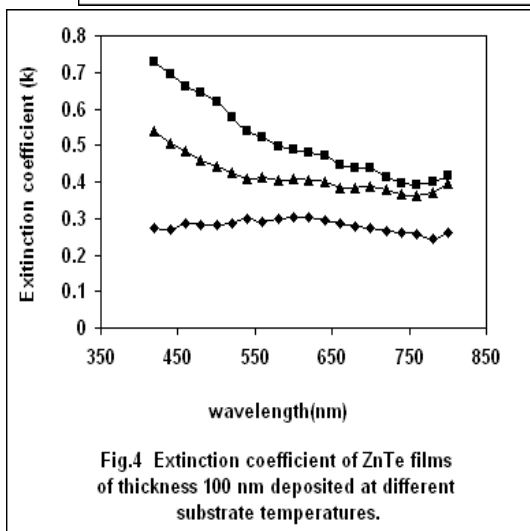
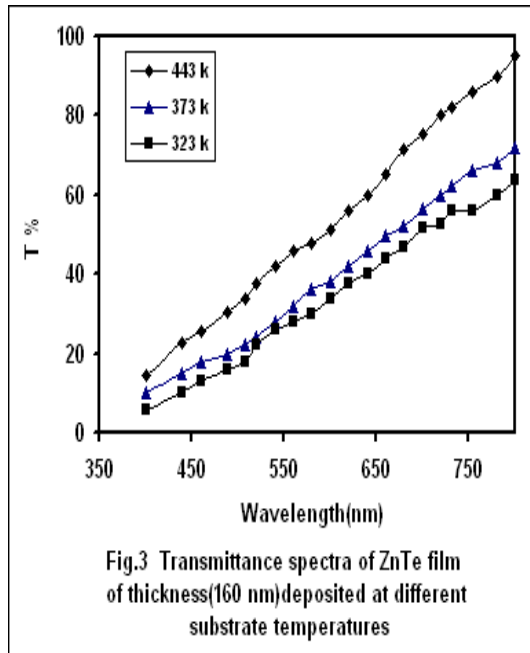
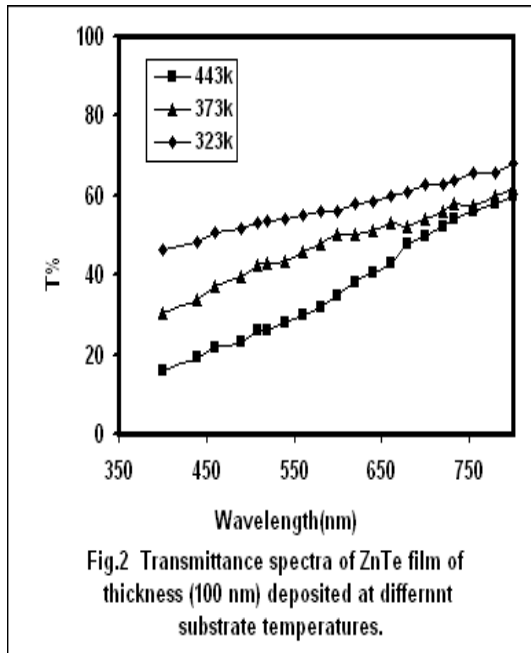
:The extinction coefficient (k_f) can be calculated from the relation

$$k_f = \frac{2.303\lambda \left(\frac{1}{T_0} \right)}{4\pi t} \quad (2) \dots\dots\dots$$

.Where T₀ is the transmittance and t is the thickness of the film
The refractive indices were calculated using Manifaciers formula[23] by the iterative :method

$$T_0 = \frac{16n n_g n^2 \exp(-\alpha t)}{R^2 + R_2^2 \exp(-2\alpha t) + 2R_1 R_2 \exp(-\alpha t) \cos\left(\frac{4\pi n t}{\lambda}\right)} \quad (3).....$$

Where $R_1=(n+n_a)(n_g+1)$, $R_2=(n-n_a)(n_g-1)$ are the absorption coefficient n , n_a and n_g :
 are the refractive indices of the film , air and substrate respectively
 Figures 3,4,5 and 6 show the variation of k and n with wavelength for ZnTe films of thickness 100 nm and 160 nm for different substrate temperatures. These optical constants(k and n)are found to be very sensitive to the substrate temperature of the film. The refractive index n decreases monotonically with increasing substrate temperature. This was found to be most noticeable near the absorption edge. An unexpected decrease of n was observed at shorter wavelengths, which have also been reported for ZnTe[by various investigators
 Figure 6 and 7 depict the variation of square of $(\alpha h\nu)$ versus photon energy($h\nu$) for ZnTe films of the thickness 100 and 160 nm for different substrate temperatures $T_s = 323, 393$ and 443 K respectively. The optical band gap energy has been evaluated by extrapolating the linear portion of the curve to the energy axis and the corresponding values with respect to the substrate temperature were given in table 2



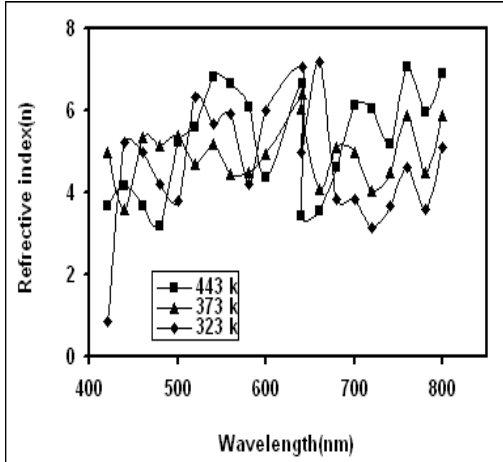


Fig.6 Refractive of ZnTe films of thickness 100 nm deposited at different substrate temperatures.

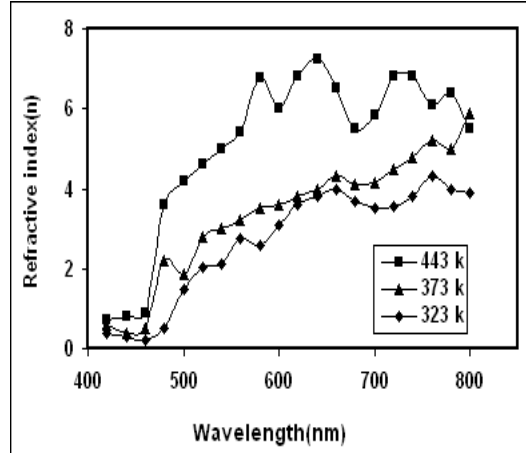


Fig.7 Refractive index of ZnTe films of thickness 160 nm deposited at different substrate temperatures

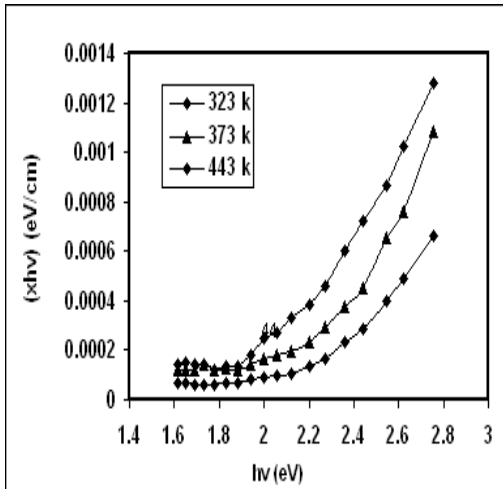


Fig.8 The dependence of () on hv for ZnTe films of thickness 100 nm deposited at different substrate temperatures

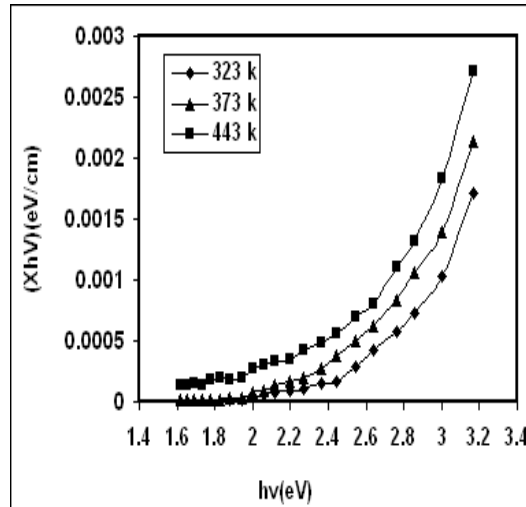


Fig.9 The dependence of () on hv for ZnTe films of thickness 160 nm deposited at different substrate temperatures

Table 2 The band gap for ZnTe films of thickness 100 and 160 nm deposited at different substrate temperatures

| Substrate (Temperature(K | Band gap energy of 100 (nm)(eV | Band gap energy of (160 nm)(eV |
|--------------------------|--------------------------------|--------------------------------|
| 323 | 2.25 | 2.15 |

| | | |
|-----|------|------|
| 393 | 2.10 | 2.06 |
| 443 | 2.05 | 2 |

The direct band gap decreases with increase of substrate temperature and thickness of the films. The decrease of direct band gap with increase of substrate temperature and thickness is attributed to an increase of particle size and increase of lattice constant [11]. From the microstructural analysis it is observed that the particle size increases with the increases of substrate temperature. The decrease in optical band gap with increase in film thickness is due to the increased grain size of the higher thickness films.

.Conclusion 4

ZnTe thin films were deposited onto well-cleaned glass substrates by vacuum evaporation. The X-ray diffraction analysis indicates that the crystalline nature of the film increases with increase in the substrate temperature. From the transmission spectra, the transmission is found to decrease with increase of substrate temperature and thickness. The optical transition in ZnTe films is direct and allowed type. The optical band gap energy shows an inverse dependence on substrate temperature and thickness.

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